

ABSTRACT

APPARATUS FOR TREATMENT OF EXHAUST GASES CONTAINING HYDROGEN

An apparatus for treatment of exhaust gases containing hydrogen which permits always stable treatment with certainty of the exhaust gases from a semiconductor manufacturing line or the like irrespective of violent fluctuations in the flow rate of the exhaust gases, without having adverse effects on the operation of the semiconductor manufacturing line.

The apparatus comprises:

an ejector-type vacuum generator (7) having a suction port (7b) connected to the discharge source of exhaust gases containing hydrogen and having a drive fluid supply port(7a) connected to an oxygen supply source,

a hydrogen-oxygen reactor provided with a catalyst and connected to a drive fluid discharge port (7c) of the vacuum generator (7), and

a drain reservoir (9,10) connected to an outlet of the reactor for storing water discharged therefrom.

FIG. 1



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